

**SURFACE TREATMENT OF A DRY-DEVELOPED HARD MASK
AND SURFACE TREATMENT COMPOSITIONS USED THEREFOR**

ABSTRACT OF THE DISCLOSURE

5 A surface treatment process includes rinsing a substrate after a dry
development process to remove residual resist material prior to patterning a hard
mask layer. An amorphous carbon hard mask is dry developed and thereafter, the
surface treatment includes an aqueous ammonium hydroxide and hydrogen peroxide
composition. While the composition acts as a solvent to the resist, the composition
10 is selective to the amorphous carbon hard mask and the surface under the hard
mask.

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